Application No. 10/501,089
Reply to Office Action of May 8, 2007

AMENDMENTS TO THE CLAIMS

- 1. (Currently amended) A process for the selective removal of sulphur compounds from synthesis gas containing at least 5% carbon monoxide, at least 5% hydrogen, [[and]] at least 0.5% carbon dioxide and optionally containing water in a concentration up to saturation at a pressure of at least 15 bar comprising contacting the synthesis gas at a maximum contact temperature of 100°C with an absorbent comprising Cu/ZnO compounds [[and]] which has been activated with a reducing gas.
- (Currently amended) Process The process of claim 1, wherein the sulphur compounds comprise HzS and COS.
- 3. (Currently amended) Process according to The process of claim 1, wherein the synthesis gas contains H2S in an amount effective for suppression of metal dusting of metals in contact with the synthesis gas within a temperature range between 300°C to Boudouard temperature of the synthesis gas.

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